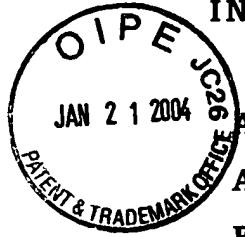


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



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JAN 26 2004  
TC 1700

Appl. No. : 09/919,868  
Applicant : Yen-Ting Lu  
Filed : August 2, 2001  
TC/A.U. : 1756  
Title : **METHOD FOR REDUCING LINE EDGE  
ROUGHNESS OF PATTERNED PHOTORESIST**  
Examiner : YOUNG, CHRISTOPHER G  
Docket No. : 4425-168

Honorable Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Sir:

In response to the Official Action mailed on October 21, 2003,  
please reconsider the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of  
claims which begin on page 2 of this paper.

**Remarks/Arguments** begin on page 8 of this paper.